Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	46365	(GaN or (gallium adj nitride))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 12:45
S2	227928	(dry adj etching) or RIE or (reactive adj ion adj etching)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 12:46
S3	91357	(contaminant or residual or residue) with metal	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 12:46
S4	3512	S3 and S2	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 12:47
S5	86	S4 and S1	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 12:50
S6	2	"20070018284".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 13:01
S7	5324	metal adj contamination	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 13:01

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S8	643	S7 and S2	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 13:03
S9	181	S8 and (wet adj (etching or etch))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON ,	2007/04/17 13:11
S10	7	(("5814157") or ("5919715") or ("2001018271")).PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/17 13:15
S11	3	("2003218085").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/17 13:16
S12	2	("5814157").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/17 15:06
S13	2	("200118271").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/17 15:07
S14	4	(("5919715") or ("5814157")).PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/17 15:08
S15	2	("5919715").URPN.	USPAT	OR	ON	2007/04/17 15:08

S16	7	("4050954" "5143103" "5286657" "5382296" "5464480" "5470393" "5472513").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/04/17 15:12
S17	13	("5472513").URPN.	USPAT	OR	ON	2007/04/17 15:12
S18	3	("5814157").URPN.	USPAT	OR	ON	2007/04/17 15:18
S19	3	("5814157").URPN.	USPAT	OR -	ON	2007/04/17 15:18
S20	12739	(metallic or metal) adj (contaminant or contamination)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 16:42
S21	0	S20 near (dry adj (etch or etching))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/17 16:45
S22	1	S20 near (RIE or (reactive adj ion adj etching))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 10:44
S23	3132	halogen near7 plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR ·	ON	2007/04/18 10:44
S24	986	S23 near7 (etch or etching)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 10:45
S25	56	S24 and (metal near7 (contaminant or contaminant))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR.	ON	2007/04/18 15:40

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S26	2	"5814157".PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2007/04/18 14:48
S27	2	"6413627".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 14:55
S28	19	(gallium near5 nitride) near8 ingot	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	.OR	ON	2007/04/18 14:56
S29	40385	(GaN (gallium near5 nitride) near8 ingot)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 14:56
S30	93	((GaN (gallium near5 nitride)) near8 ingot)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 14:56
531	67	S30 and (polish\$3 CMP)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 14:57
S32	61	S31 and (etch\$3 clean\$3 wash\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 16:54

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S33	256	polish\$4 near (dry adj (etch or etching))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 15:14
S34	37	S33 and (GaN or (gallium adj nitride))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 15:15
S35	19	S25 and polish\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2007/04/18 15:40
S36	29402	metal near4 (contaminant or contamination)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 16:16
S37	954	S36 and (dry adj etching)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 16:17
S38	448	S37 and polish\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 16:17
S39	46365	GaN or (gallium adj nitride)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON ·	2007/04/18 16:17

S40	7	S39 and S38	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 16:17
S41		jp-2001244240-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 16:55
S42	2	jp-2003218085-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/18 16:55